

Search History:

Limited Classification Search

The Patent Analyst performed a limited classification search within the following US, IPC, CPC, ECLA, or F-Term classification areas:

CPC Class/Subclass(es): B41J 2/06; B41J 2/01; B41J 2/09; C12Q 1/00; C23C 4/12; G01N 27/44739; G01N 27/44791; G01N 27/62; G01N 30/6095; H05K 3/125 (2020.08)

IPC (8) Class/Subclass(es): B41J 2/06; B41J 2/09; C12Q 1/00; C23C 4/12; G01N 27/62; H05K 3/12 (2020.01)

U.S. Class/Subclass(es): 210/243; 250/288; 347/55; 347/77; 427/458; 427/466; 435/6.12

See Global Search Results.

Global Patent Literature Text Search

The Patent Analyst performed the following global text search, which was not limited by classification but may or may not have been limited by other criteria:

Questel Orbit: <https://www.orbit.com>

#	Search query	Results
1	((FLOW S REGULAT+) AND (NANODROPLET+) AND (NOZZLE+) AND (ELECTRODE+) AND (LENS+) AND (RESERVOIR+))/TI/AB/CLMS/DESC/ODES/OBJ/ADB/ICLM/KEYW/TX	2
2	((FLOW S REGULAT+) AND (NANO+ S DROPLET+) AND (NOZZLE+) AND (ELECTRODE+) AND (LENS+) AND (RESERVOIR+))/TI/AB/CLMS/DESC/ODES/OBJ/ADB/ICLM/KEYW/TX	100
3	2 NOT 1	98
4	((FLOW S CONTROL+) AND (NANO+ S DROPLET+) AND (NOZZLE+) AND (ELECTRODE+) AND (LENS+) AND (RESERVOIR+) AND (FILAMENT+))/TI/AB/CLMS/DESC/ODES/OBJ/ADB/ICLM/KEYW/TX	84
5	4 NOT 3	46
6	((FLOW S CONTROL+) AND (NANO+ S DROPLET+) AND (NOZZLE+ S ALIGN+) AND (ELECTRODE+) AND (RESERVOIR+) AND (FILAMENT+))/TI/AB/CLMS/DESC/ODES/OBJ/ADB/ICLM/KEYW/TX	40
7	*MEM "home/QPTLD093/homequicklist" /XPN /APID	13
8	((FLOW S CONTROL+) AND (NANO+ S DROPLET+) AND (NOZZLE+ S ALIGN+) AND (ELECTRODE+) AND (RESERVOIR+) AND (GAP+))/TI/AB/CLMS/DESC/ODES/OBJ/ADB/ICLM/KEYW/TX	101
9	8 NOT 3	84
10	(347077)/PCL	255

11	10 AND (NOZZLE+) AND (ELECTRODE+)	89
12	10 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	10
13	(347055)/PCL	909
14	13 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	40
15	(427466)/PCL	460
16	15 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	2
17	(427458)/PCL	523
18	17 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	3
19	(435006120)/PCL	12335
20	19 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	1
21	(250288)/PCL	2758
22	21 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	13
23	(210243)/PCL	612
24	23 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	6
25	(C23C-004/12)/IPC	7321
26	25 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	5
27	(C12Q-001/00)/IPC	20506
28	27 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	4
29	(G01N-027/447)/IPC	12360
30	29 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	29
31	(G01N-027/62)/IPC	18445
32	31 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	15
33	(B41J-002/09)/IPC	735
34	33 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	19
35	(B41J-002/06)/IPC	2687
36	35 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	71
37	(B41J-002/01)/IPC	74957
38	37 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	146
39	(B41J-002/005)/IPC	1684

40	39 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	11
41	(H05K-003/12)/IPC	12059
42	41 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	11
43	(H05K-003/125)/CPC	1082
44	43 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	3
45	(G01N-027/44739)/CPC	153
46	(G01N-027/44791)/CPC	1165
47	46 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	15
48	(G01N-027/62)/CPC	4162
49	48 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	5
50	(C23C-004/12)/CPC	3386
51	50 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	3
52	(C12Q-001/00)/CPC	4139
53	52 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	2
54	(G01N-030/6095)/CPC	717
55	54 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	8
56	(B41J-002/01)/CPC	5436
57	56 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	11
58	(B41J-002/06)/CPC	818
59	58 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	36
60	(B41J-002/09)/CPC	385
61	60 AND (NOZZLE+) AND (ELECTRODE+) AND (RESERVOIR+)	12

Google Patents: <https://patents.google.com>

#	Search query	Results
1	"nanodroplets" "nozzle" "electrodes"	62
2	"nozzle" "electrodes" (nanodroplets)	90
3	"nozzle" "electrodes" (nanodroplets) (reservoir)	55
4	"nozzle" (print) (nanodroplets) (reservoir) (electrodes)	27
5	(nozzle) (print) (nanodroplets) (reservoir) (electrodes)	38
6	(nozzle) (print) (droplets) (reservoir) (electrodes)	43454

7	(nozzle) (print) (droplets) (reservoir) (electrodes) (substrate) (nano)	2087
8	(nozzle) (print) (droplets) (reservoir) (electrodes) (substrate) (nano) (align)	1271
9	(nozzle) (print) (droplets) (reservoir) (electrodes) (voltage) (substrate) (nano) (align)	767
10	(nozzle) (print) (droplets) (reservoir) (filament gap) (electrodes) (voltage) (substrate) (nano) (align)	70

Computer Accessed Text Databases Searched

The Patent Analyst searched the following computer accessed text databases:

Proquest: <http://www.proquest.com/>

#	Search query	Results
1	(nozzle) (print) (nanodroplets) (reservoir) (gap) (electrodes) (substrate)	308
2	(nozzle) (print) (nanodroplets) (reservoir) (gap) (electrodes) (substrate) (align)	206
3	(nozzle) (print) (nanodroplets) (reservoir) (gap) (electrodes) (substrate) (align) (voltage)	199
4	(nozzle) (print) (droplets) (reservoir) (gap) (electrodes) (substrate) (align) (voltage)	3386
5	(nozzle) (print) (droplets) (reservoir) (gap) (electrodes) (substrate) (align) (voltage) (nano)	2387

Google Scholar: <https://scholar.google.com/>

#	Search query	Results
1	(nozzle) (print) (droplets) (reservoir) (filament gap) (electrodes) (voltage) (substrate) (nano) (align)	808
2	(nozzle) (print) (droplets) (reservoir) (gap) (electrodes) (voltage) (substrate) (nano) (align)	2580
3	(nozzle) (print) (nanodroplets) (reservoir) (gap) (electrodes) (voltage) (substrate) (align)	149
4	(nozzle) (print) (nanodroplets) (reservoir) (gap) (electrodes) (substrate) (align)	162
5	(nozzle) (print) (nanodroplets) (reservoir) (gap) (electrodes) (substrate)	214

Date search was completed: 01 August 2020

JN/CC